

EV372467541

Sheet 1 of 1

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.  
M140-273

SERIAL NO.  
09/502,693

LIST OF ART CITED BY APPLICANT  
(Use several sheets if necessary)

APPLICANT  
Micron Technology, Inc.

FILING DATE  
February 11, 2000

GROUP  
3684

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL	0 172 445 A1	07/1985	EPO (Statement of Relevance provided in IDS)			x	
	AM	0 682 382 A2	04/1995	EPO (Statement of Relevance provided in IDS)			x	
	AN	0 682 382 A3	05/1995	EPO (Statement of Relevance provided in IDS)			x	
	AO							
	AP							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

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PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
M140-273SERIAL NO.  
09/502,693LIST OF ART CITED BY APPLICANT  
(Use several sheets if necessary)APPLICANT  
Micron Technology, Inc.FILING DATE  
February 11, 2000GROUP  
3662

## U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,361,403	11/1994	Devi	455	74	
	AB	5,423,074	06/1995	Devi	455	74	
	AC	4,283,646	11/1988	Matsuzaki	340	572	
	AD	5,072,194	12/1991	Chevalier	330	260	
	AE	5,300,896	04/1994	Sociserman	330	260	
	AF	5,365,192	11/1994	Wagner et al.	330	252	
	AG	5,394,159	02/1995	Schneider et al.	343		
	AH	4,190,838	02/1980	Kemp	343	15	
	AI	5,511,090	04/1996	Denton et al.	375	205	
	AJ						
	AK						

## FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
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	AL	0 172 445 A1	07/1985	EPO				
	AM	0 682 382 A2	04/1995	EPO				
	AN	0 682 382 A3	05/1995	EPO				
	AO	DE 3212876 A1	04/1983	Germany				
	AP	0 616 429 A1	01/1994	EPO				

## OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AR		N.J. Woods et al., "One micrometre scale self-aligned cobalt disilicide Schottky barrier diodes", ELECTRONICS LETTERS, IEE Stevenage, GB.
			Vol. 31, No. 21, Oct. 1995, pages 1878-1880
	AS		Shenai Krishna, "Characteristics of LPCVD WSi2N-Si Schottky Contacts", IEEE ELECTRON DEVICE LETTERS, U.S. IEEE INC. N.Y., Vol. 12
			No. 4, April 1991, pages 169-171
	AT		

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DATE CONSIDERED

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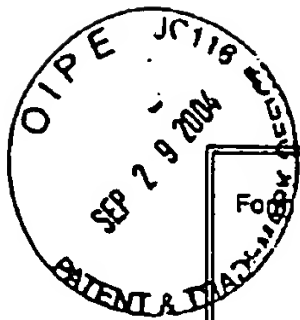


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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO. M140-273		SERIAL NO. 09/502,693		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Micro Technology, Inc.				
				FILING DATE February 11, 2000		GROUP 2687		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
✓	AA	5,640,151	06/17/97	Reis et al.	340	825.34		
✓	AB	4,384,288	05/17/83	Walton	340	825.34		
✓	AC	4,514,731	04/30/85	Felch et al.	340	825.08		
✓	AD	4,868,908	09/19/89	Pless et al.	323	267		
✓	AE	5,103,156	04/07/92	Jones et al.	320	35		
✓	AF	5,406,297	04/11/95	Carwell et al.	343	741		
✓	AG	5,485,520	01/16/96	Cham et al.	380			
	AH							
	AI							
	AJ							
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FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
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	AM							
	AN							
	AO							
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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EXAMINER <i>Phil J. [Signature]</i>				DATE CONSIDERED <i>2/2/2005</i>				
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LIST OF ART CITED BY APPLICANT <small>(Use several sheets if necessary)</small>				APPLICANT: Micron Technology, Inc. <b>RECEIVED</b>			
				FILING DATE February 11, 2000		OCT 8 2004 GROUP 3602-2684 Technology Center 2000	
U.S. PATENT DOCUMENTS							
Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
a	AA	4,843,354	06/1989	Fuller et al.	333	81	
~	AB	5,448,770	09/1995	Hietala et al.	455	125	
~	AC	5,696,025	12/1997	Violette et al.	437	175	
~	AD	5,741,462	04/1998	Nova et al.	422	68.1	
~	AE	3,694,776	09/1972	Linder	333	17	
~	AF	3,921,094	11/1975	Schaible	331	1	
~	AG	5,121,407	06/1992	Partyka et al.	375	1	
~	AH	5,334,951	08/1994	Hogeboom	331	1	
~	AJ	5,705,947	01/1998	Jeong	327	270	
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation Yes      No
	AJ						
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM						
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	AM						
	AO						
	AO						
EXAMINER <i>[Signature]</i>		DATE CONSIDERED <i>2/2/2005</i>					
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M140-273		SERIAL NO. 09/302,693	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Micron Technology, Inc.		FILING DATE February 11, 2000	
				GROUP 3662 2687			
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
~	AA	5,361,403	11/1994	Dent	455	74	
~	AB	5,423,074	06/1995	Dent	455	74	
~	AC	4,783,646	11.1988	Matsuzaki	340	572	
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~	AE	5,300,896	04/1994	Suesserman	330	260	
~	AF	5,365,192	11/1994	Wagner et al.	330	252	
~	AG	5,394,159	02/1995	Schneider et al.	343	700	
~	AH	4,190,838	02/1980	Kemp	343	18	
~	AI	5,511,090	04/1996	Denton et al.	375	205	
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~	AM	0 682 382 A2	04/1995	EPO			
~	AN	0 682 382 A3	05/1995	EPO			
	AO	DE 3212876 A1	04/1985	Germany			
	AP	0 616 429 A1	01/1994	EPO			
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~	AR		N.J. Woods et al., "One micrometre scale self-aligned cobalt disilicide Schottky barrier diodes", ELECTRONICS LETTERS, IEE Stevenage, GB.				
			Vol. 31, No. 21, Oct. 1995, pages 1878-1880				
~	AS		Shenai Krishna, "Characteristics of LPCVD WSi2/N-Si Schottky Contacts", IEEE ELECTRONIC DEVICE LETTERS, US, IEEE INC. N.Y., Vol. 12				
			No. 4, April 1991, pages 169-171				
	AT						
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P. S. Subramanian				6/18/07			
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